

ABSTRACT

Present disclosure provides a carrying device and a semiconductor processing apparatus. In this carrying device, a second gas distribution passage group surrounds the periphery of an annular passage; a plurality of first connecting passages are located in the space enclosed by the annular passage, one end of each first connecting passage serves as a gas inlet, and the other end is connected to the annular passage; the annular passage and the second gas distribution passage group are connected through a plurality of second connecting passages; and, the plurality of second connecting passages are spaced apart along a circumferential direction of the annular passage. This solution can effectively improve the distribution uniformity of the purging gas blown towards the edge region of the wafer in the circumferential direction, thereby improving process uniformity.